

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|------|--|---|------------------|---------|------------------|
| L2 | 0 | semiconductor substrate with one square meter | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 12:38 |
| L3 | 2 | semiconductor same substrate with one square meter | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 12:38 |
| L4 | 1666 | (438/149).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/03/20 12:54 |
| L5 | 1355 | (438/151).CCLS. | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2006/03/20 12:54 |
| S1 | 5 | mask near area with well adj known | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 14:20 |
| S2 | 0 | mask near area with known same impant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 14:20 |
| S3 | 0 | mask near area with known and impant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 14:20 |
| S4 | 0 | mask with area with known and impant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 14:20 |

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| S5 | 153 | mask with area with known and implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 14:21 |
| S6 | 40 | mask with area with known same implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 15:14 |
| S7 | 0 | mask with area with design with known same implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 15:14 |
| S8 | 20 | mask with area with design with known | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 16:51 |
| S9 | 84 | mask near area with known | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 16:52 |
| S10 | 4 | mask near area with known same implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 16:54 |
| S11 | 0 | mask near percent with area with known | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 16:55 |
| S12 | 1 | mask with percent with area with known | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 16:55 |

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| S13 | 151 | mask with percent with area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 16:56 |
| S14 | 8 | mask with percent with area and implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 16:59 |
| S15 | 12 | mask near percent with area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 10:13 |
| S16 | 1 | mask near percent with area and semiconductor | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 17:33 |
| S17 | 1 | mask near percent near area and semiconductor | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 17:34 |
| S18 | 5 | mask near percent near area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 17:41 |
| S19 | 5 | ("1" or "2" or "3" or "4" or "5" or "6" or "7" or "8" or "9" or "10" or "11" or "12" or "13" or "14" or "15") adj percent with mask near area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 17:44 |
| S20 | 5 | ("1" or "2" or "3" or "4" or "5" or "6" or "7" or "8" or "9" or "10" or "11" or "12" or "13" or "14" or "15") near percent with mask near area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 17:46 |

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| S21 | 12 | ("1" or "2" or "3" or "4" or "5" or "6" or "7" or "8" or "9" or "10" or "11" or "12" or "13" or "14" or "15") near percent same mask near area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 17:58 |
| S22 | 7 | ("1" or "2" or "3" or "4" or "5" or "6" or "7" or "8" or "9" or "10" or "11" or "12" or "13" or "14" or "15") near percent same mask area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:19 |
| S23 | 90 | dop\$3 same mask area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:20 |
| S24 | 0 | dop\$3 same percent with mask area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:20 |
| S25 | 0 | dop\$3 same percent same mask area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:21 |
| S26 | 90 | dop\$3 same mask adj area | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:23 |
| S27 | 0 | dop\$3 same mask adj area with percent | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:21 |
| S28 | 0 | dop\$3 same mask adj area with "%" | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:22 |

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| S29 | 30 | dop\$3 same mask adj area and kev | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:27 |
| S30 | 1 | implant with mask adj area and kev | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:29 |
| S31 | 1234 | mask\$3 with percentage | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:30 |
| S32 | 14 | mask\$3 with percentage same implant | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:34 |
| S33 | 0 | mask\$3 near percent\$3 same implant | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:34 |
| S34 | 186 | mask\$3 near percent\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:34 |
| S35 | 55 | mask\$3 near percent\$3 and semiconductor | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:34 |
| S36 | 0 | mask\$3 near percent\$3 and semiconductor and kev | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:34 |

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| S37 | 5 | mask\$3 near percent\$3 and semiconductor and implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/09 18:35 |
| S38 | 105 | resist with area with proportion | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 15:48 |
| S39 | 7 | resist with area with proportion same mask | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:02 |
| S40 | 1409 | resist with area with substrate same mask | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:02 |
| S41 | 1094 | resist with area with substrate with mask | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:03 |
| S42 | 12 | resist adj area with substrate with mask | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:02 |
| S43 | 209 | resist with area with substrate with mask same implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:04 |
| S44 | 5 | resist near area with substrate with mask same implant\$6 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:04 |

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| S45 | 0 | resist near area with substrate with mask with percent\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:05 |
| S46 | 8 | resist near area with percent\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:06 |
| S47 | 76 | resist with area and coverage with substrate | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:06 |
| S48 | 10 | resist with area same coverage with substrate | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/02/10 17:06 |
| S49 | 3946 | tft and mask and implant\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 10:13 |
| S50 | 1 | tft and mask with area with known and implant\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 10:14 |
| S51 | 125 | semiconductor and mask with area with known and implant\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 10:17 |
| S52 | 200 | tft and mask with known and implant\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 10:20 |

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| S53 | 11 | tft and mask with area same known and implant\$3 | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 11:10 |
| S54 | 38 | substrate with one square meter | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 11:11 |
| S55 | 0 | tft substrate with one square meter | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 11:11 |
| S56 | 6 | tft and substrate with one square meter | US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB | ADJ | OFF | 2006/03/20 12:38 |